

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2507		PRIORITY SERIAL NO. 10/092,874	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Micron Technology, Inc.			
					PRIORITY FILING DATE March 5, 2002		PRIORITY GROUP 2814	
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	US 2002/0045130 A1	4/18/02	Nitta et al.				
	AB	US 2003/0008246 A1	1/9/03	Cheng et al.				
	AC	6,403,280	6/11/02	Yamahara et al.				
	AD	6,136,511	10/24/00	Reinberg et al.				
	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AK							
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM	"Chemically Amplified Photoresists" , IBM: http://www.almaden.ibm.com/sr/projects/sub100nm/objectives/ca/						
	AN	"Imaging of photogenerated acid in a chemically amplified photoresist" : S. J. Bukofsky et al; 1998 American Institute of Physics, Vol. 73, No. 3, 20 July 1998, pp. 408-410						
	AO							
	AP							
EXAMINER					DATE CONSIDERED 7/7/04			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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